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Declaration under Rule 4.17:

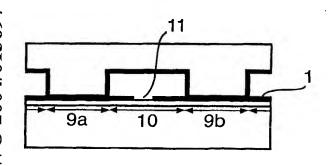
as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii)) for the following designations AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW, ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG)

Published:

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- (88) Date of publication of the international search report: 15 July 2004

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(54) Title: MICRO-CONTACT PRINTING METHOD



(57) Abstract: The invention relates to micro-contact printing, wherein a self-assembled monolayer(SAM)-forming molecular species (1) is applied to a surface (2) of an article (3). The SAM-forming species (1) comprise a polar functional group that is exposed when the species (1) form a monolayer. This enables said printing method to be performed in vacuum or in a gaseous atmosphere, preferably in air. The invention also relates to an article having a surface comprising at least one isolated region of a SAM having a lateral dimension within the range of from 1 to 100 nm. Furthermore, the invention relates to a method for producing at least one nanowire, or a grid of nanowires, having a lateral dimension within the range of from 1 to 100 nm.





INTERNATIONAL SEARCH REPORT

tional Application No PCT/IB 03/03060

A. CLASSIFICATION OF SUBJECT MATTER IPC 7 G03F7/00 B05D1/28

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols) IPC 7 G03F B05D

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the International search (name of data base and, where practical, search terms used)

EPO-Internal, COMPENDEX, WPI Data, INSPEC, IBM-TDB

Category •	Cliation of document, with Indication, where appropriate, of the r	Relevant to claim No.			
X	"FABRICATION OF GOLD NANOSTRUCTULITHOGRAPHY WITH SELF-ASSEMBLED MONOLAYERS" IBM TECHNICAL DISCLOSURE BULLETICORP. NEW YORK, US, vol. 39, no. 12, 1 December 1996 (1996-12-01), pa 235-238, XP000686075 ISSN: 0018-8689	8,13			
A	the whole document	- /	9		
Y Further documents are listed in the continuation of box C. X Patent family members are listed in annex.					
"A" docume consid "E" earlier d filling d "L" docume which i chatio "O" docume other n "P" docume later th	nt which may throw doubts on priority claim(s) or so cited to establish the publication date of another or other special reason (as specified) in treferring to an oral disclosure, use, exhibition or neans at published prior to the International filling date but an the priority date claimed	 *T* later document published after the International filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention *X* document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is taken alone *Y* document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person sidiled in the art. *&* document member of the same patent family 			
	ctual completion of the international search April 2004	Date of mailing of the international sear	ch report		
Name and m	alling address of the ISA European Palent Office, P.B. 5818 Patentlaan 2 NL - 2280 HV Rijswijk Tel. (+31-70) 340-2040, Tx. 31 651 epo nl, Fax: (+31-70) 340-3016	Authorized officer Haenisch, U			

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INTERNATIONAL SEARCH REPORT

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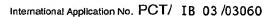
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Category °	C.(Continuation) DOCUMENTS CONSIDERED TO BE RELEVANT Category Citation of document, with indication, where appropriate, of the relevant passages Relevant to claim No.					
Y	HUANG JET AL: "Photopatterning of self-assembled alkanethiolate monolayers on gold. A simple monolayer photoresist utilizing aqueous chemistry" LANGMUIR; LANGMUIR MAR 1994, vol. 10, no. 3, March 1994 (1994-03),	9				
Y	pages 626-628, XP002278004 the whole document GUCKEL K ET AL: "Fabrication of assembled micromechanical components via deep X-ray lithography"	9				
	PROCEÉDINGS OF THE WORKSHOP ON MICRO ELECTRO MECHANICAL SYSTEMS. INVESTIGATION OF MICRO STRUCTURES, SENSORS, ACTUATORS, MACHINES AND ROBOTS. NARA, JP., JAN. 30 - FEB. 2, 1991, NEW YORK, IEEE, US, vol. WORKSHOP 4, 30 January 1991 (1991-01-30), pages 74-79, XP010039609 ISBN: 0-87942-641-1 the whole document	·				
A	YOUNAN XIA ET AL: "USE OF CONTROLLED REACTIVE SPREADING OF LIQUID ALKANETHIOL ON THE SURFACE OF GOLD TO MODIFY THE SIZE OF FEATURES PRODUCED BY MICROCONTACT PRINTING" JOURNAL OF THE AMERICAN CHEMICAL SOCIETY, AMERICAN CHEMICAL SOCIETY, WASHINGTON, DC, US, vol. 117, no. 11, 22 March 1995 (1995-03-22), pages 3274-3275, XP000573923 ISSN: 0002-7863 the whole document					
A	E. DELAMARCHE ET AL.: "POSITIVE MICROCONTACT PRINTING" JOURNAL OF THE AMERICAN CHEMICAL SOCIETY, AMERICAN CHEMICAL SOCIETY, WASHINGTON, DC, US, vol. 124, no. 15, 21 March 2002 (2002-03-21), pages 3834-3835, XP002278005 ISSN: 0002-7863 cited in the application the whole document	2				
A	US 6 413 587 B1 (ABBOTT NICHOLAS ET AL) 2 July 2002 (2002-07-02)					

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lernational application No. PCT/IB 03/03060

Box I	Observations where certain claims were found unsearchable (Continuation of item 1 of first sheet)
This Inte	ernational Search Report has not been established in respect of certain claims under Article 17(2)(a) for the following reasons:
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1.	Claims Nos.: because they relate to subject matter not required to be searched by this Authority, namely:
1	• • • • • • • • • • • • • • • • • • • •
1	
2.	Claims Nos.:
	because they relate to parts of the International Application that do not comply with the prescribed requirements to such an extent that no meaningful international Search can be carried out, specifically:
<u> </u>	•
3.	Claims Nos.: because they are dependent claims and are not drafted in accordance with the second and third sentences of Rule 6.4(a).
Box II	Observations where unity of invention is lacking (Continuation of item 2 of first sheet)
This Inte	ernational Searching Authority found multiple inventions in this international application, as follows:
i	
l	see additional sheet
1.	As all required additional search fees were timely paid by the applicant, this International Search Report covers all searchable claims.
	searchable Gains.
2. X	As all searchable claims could be searched without effort justifying an additional fee, this Authority did not invite payment
	of any additional fee.
з. 🦳	As only some of the required additional search fees were timely paid by the applicant, this International Search Report
ـــا	covers only those claims for which fees were paid, specifically claims Nos.:
4.	No required additional search fees were timely paid by the applicant. Consequently, this international Search Report is
	restricted to the invention first mentioned in the claims; it is covered by claims Nos.:
Remark	on Protest The additional search fees were accompanied by the applicant's protest.
	No protest accompanied the payment of additional search fees.



FURTHER INFORMATION CONTINUED FROM PCT/ISA/ 210

This International Searching Authority found multiple (groups of) inventions in this international application, as follows:

1. claims: 1-7,10-12

microcontact printing methods for applying self-assembled monolayers involving controlled spreading of the monolayers,

2. claims: 8,9,13

method for producing nanowires using narrow (1-100nm) monolayer patterns as etch mask,.





INTERNATIONAL SEARCH REPORT

In ptional Application No PCT/IB 03/03060

Pa cited	atent document d in search report		Publication date		Patent family member(s)		Publication date
US	6413587	B1	02-07-2002	US	2002071943	A1	13-06-2002
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